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Most Frequently Occurring Classifications of Patents Returned
From A Search of 10799762 on January 26, 2005

Original Classifications

3 430/280.1
2 313/512
2 430/312

Cross-Reference Classifications

4 313/502
4 522/170
4 522/25
3 522/31
2 250/239
2 252/301.36
2 257/100
2 264/137
2 264/495
2 264/496
2 313/501
2 349/153
2 385/92
2 427/553
2 427/66
2 430/270.1
2 430/273.1
2 430/281.1
2 430/288.1
2 430/315
2 430/319
2 430/325
2 430/327
2 430/945
2 473/378
2 522/100
2 522/15
2 522/29
2 522/99
2 526/222
2 528/409
2 528/90

Combined Classifications

5 313/502
5 522/170
4 522/25
4 522/31
3 264/496
3 313/512
3 385/92
3 430/270.1
3 430/280.1
3 430/312
3 430/315
2 156/273.3
2 250/239
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2 252/301.36
2 257/100
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2 313/501
2 313/503
2 349/153
2 385/88
2 427/553
2 427/66
2 428/457
2 428/690
2 430/273.1
2 430/281.1
2 430/288.1
2 430/319
2 430/325
2 430/327
2 430/945
2 473/378
2 522/100
2 522/15
2 522/28
2 522/29
2 522/99
2 526/222
2 528/409
2 528/90

Titles of Most Frequently Occurring Classifications of Patents Returned
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5 313/502 (1 OR, 4 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/483 WITH LUMINESCENT SOLID OR LIQUID MATERIAL
313/498 .Solid-state type
313/502 ..With phosphor embedding material

5 522/170 (1 OR, 4 XR)
Class 522 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
OF THE CLASS 520 SERIES
522/1 .COMPOSITIONS TO BE POLYMERIZED BY WAVE ENERGY
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
MATERIAL; OR COMPOSITIONS TO BE MODIFIED BY WAVE ENERGY
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
MATERIAL; OR PROCESSES OF PREPARING OR TREATING A SOLID
POLYMER UTILIZING WAVE ENERGY
522/168 ..Processes of preparing a solid polymer from a
heterocyclic chalcogen monomer; or compositions therefore
522/170 ...1,2 epoxy

4 522/25 (0 OR, 4 XR)
Class 522 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
OF THE CLASS 520 SERIES
522/1 .COMPOSITIONS TO BE POLYMERIZED BY WAVE ENERGY
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
MATERIAL; OR COMPOSITIONS TO BE MODIFIED BY WAVE
ENERGY
SOLID
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
MATERIAL; OR PROCESSES OF PREPARING OR TREATING A
POLYMER UTILIZING WAVE ENERGY
522/6 ..Compositions to be polymerized or modified by
wave energy wherein said composition contains at least
one
specified rate-affecting material; or processes of
preparing or treating a solid polymer utilizing wave
energy
rate-affecting
in the presence of at least one specified
material; e.g., nitrogen containing photosensitizer,
oxygen containing photoinitiator, etc. wave energy in order to
prepare a cellular product
522/7 ...Contains two or more rate-affecting
materials, at least one of which is specified
522/25Specified rate-affecting material contains
onium group

4 522/31 (1 OR, 3 XR)
Class 522 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
OF THE CLASS 520 SERIES
522/1 .COMPOSITIONS TO BE POLYMERIZED BY WAVE ENERGY
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
MATERIAL; OR COMPOSITIONS TO BE MODIFIED BY WAVE ENERGY
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
MATERIAL; OR PROCESSES OF PREPARING OR TREATING A SOLID
POLYMER UTILIZING WAVE ENERGY
522/6 ..Compositions to be polymerized or modified by
wave energy wherein said composition contains at least
one

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energy specified rate-affecting material; or processes of preparing or treating a solid polymer utilizing wave

oxygen in the presence of at least one specified rate-affecting material; e.g., nitrogen containing photosensitizer,

522/31 containing photoinitiator, etc. wave energy in order to prepare a cellular product

...Specified rate-affecting material contains onium group

3 264/496 (1 OR, 2 XR)
Class 264 : PLASTIC AND NONMETALLIC ARTICLE SHAPING OR TREATING: PROCESSES

264/484 .Utilizing electrostatic charge, field, force (e.g., pinning, etc.)

264/494 .Polymerizing, cross-linking, or curing (e.g., utilizing ultraviolet radiation, etc.)

264/496 ..While contacting a shaping surface (e.g., in mold curing, etc.)

3 313/512 (2 OR, 1 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES

313/483 WITH LUMINESCENT SOLID OR LIQUID MATERIAL

313/498 .Solid-state type

313/512 ..With envelope or encapsulation

3 385/92 (1 OR, 2 XR)
Class 385 : OPTICAL WAVEGUIDES

385/53 WITH DISENGAGABLE MECHANICAL CONNECTOR

385/88 .Optical fiber to a nonfiber optical device connector

385/92 ..With housing

3 430/270.1 (1 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF

430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT

430/270.1 .Radiation sensitive composition or product or process of making

3 430/280.1 (3 OR, 0 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF

430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT

430/270.1 .Radiation sensitive composition or product or process of making

430/280.1 ..Radiation sensitive composition comprising oxirane ring containing component

3 430/312 (2 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF

430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT

430/311 .Making electrical device

430/312 ..Including multiple resist image formation

- 3 430/315 (1 OR, 2 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
 COMPOSITION, OR PRODUCT THEREOF
 430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
 RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR

OR

- 430/311 PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
 430/313 .Making electrical device
 ..With formation of resist image, and etching
 of substrate or material deposition
 430/315 ...Material deposition only
- 2 156/273.3 (1 OR, 1 XR)
 Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL
 MANUFACTURE
 156/1 METHODS
 156/60 .Surface bonding and/or assembly therefor
 156/272.2 ..With direct application of electrical,
 magnetic, or radiant energy to work
 156/273.3 ...Before final assembly; e.g., to cure lamina,
 etc.
- 2 250/239 (0 OR, 2 XR)
 Class 250 : RADIANT ENERGY
 250/200 PHOTOCELLS; CIRCUITS AND APPARATUS
 250/239 .Housings (in addition to cell casing)
- 2 250/551 (1 OR, 1 XR)
 Class 250 : RADIANT ENERGY
 250/200 PHOTOCELLS; CIRCUITS AND APPARATUS
 250/551 .Signal isolator
- 2 252/301.36 (0 OR, 2 XR)
 Class 252 : COMPOSITIONS
 252/301.36 INORGANIC LUMINESCENT COMPOSITIONS WITH ORGANIC
 NONLUMINESCENT MATERIAL
- 2 257/100 (0 OR, 2 XR)
 Class 257 : ACTIVE SOLID-STATE DEVICES
 257/79 INCOHERENT LIGHT EMITTER STRUCTURE
 257/100 .Encapsulated
- 2 257/98 (1 OR, 1 XR)
 Class 257 : ACTIVE SOLID-STATE DEVICES
 257/79 INCOHERENT LIGHT EMITTER STRUCTURE
 257/98 .With reflector, opaque mask, or optical
 element (e.g., lens, optical fiber, index of refraction
 matching layer, luminescent material layer, filter)
 integral with device or device enclosure or package
- 2 264/137 (0 OR, 2 XR)
 Class 264 : PLASTIC AND NONMETALLIC ARTICLE SHAPING OR
 TREATING: PROCESSES
 264/129 WITH PRINTING OR COATING OF WORKPIECE (OUT OF
 MOLD)
 264/134 .Coating or impregnating workpiece before
 molding or shaping step
 264/136 ..Impregnation of batt, sheet, or filament
 264/137 ...Heat settable impregnant
- 2 264/495 (0 OR, 2 XR)
 Class 264 : PLASTIC AND NONMETALLIC ARTICLE SHAPING OR
 TREATING: PROCESSES

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264/484 .Utilizing electrostatic charge, field, force
(e.g., pinning, etc.)

264/494 .Polymerizing, cross-linking, or curing (e.g.,
utilizing ultraviolet radiation, etc.)

264/495 ..Indefinite length articles

2 313/501 (0 OR, 2 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/483 WITH LUMINESCENT SOLID OR LIQUID MATERIAL
313/498 .Solid-state type
313/499 ..Semiconductor depletion layer type
313/501 ...Light conversion

2 313/503 (1 OR, 1 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/483 WITH LUMINESCENT SOLID OR LIQUID MATERIAL
313/498 .Solid-state type
313/503 ..With particular phosphor or electrode
material

2 349/153 (0 OR, 2 XR)
Class 349 : LIQUID CRYSTAL CELLS, ELEMENTS AND SYSTEMS
349/56 PARTICULAR STRUCTURE
349/84 .Having significant detail of cell structure
only
349/153 ..Liquid crystal seal

2 385/88 (1 OR, 1 XR)
Class 385 : OPTICAL WAVEGUIDES
385/53 WITH DISENGAGABLE MECHANICAL CONNECTOR
385/88 .Optical fiber to a nonfiber optical device
connector

2 427/553 (0 OR, 2 XR)
Class 427 : COATING PROCESSES
427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,
WAVE, OR PARTICULATE ENERGY
427/532 .Pretreatment of substrate or post-treatment of
coated substrate
427/553 ..Low energy electromagnetic radiation (e.g.,
microwave, radio wave, IR, UV, visible, actinic, laser,
etc.)

2 427/66 (0 OR, 2 XR)
Class 427 : COATING PROCESSES
427/58 ELECTRICAL PRODUCT PRODUCED
427/64 .Fluorescent or phosphorescent base coating
(e.g., cathode-ray tube, luminescent screen, etc.)
427/66 ..Electroluminescent lamp

2 428/457 (1 OR, 1 XR)
Class 428 : STOCK MATERIAL OR MISCELLANEOUS ARTICLES
428/411.1 COMPOSITE (NONSTRUCTURAL LAMINATE)
428/457 .Of metal

2 428/690 (1 OR, 1 XR)
Class 428 : STOCK MATERIAL OR MISCELLANEOUS ARTICLES
428/411.1 COMPOSITE (NONSTRUCTURAL LAMINATE)
428/688 .Of inorganic material
428/689 ..Metal-compound-containing layer
428/690 ...Fluorescent, phosphorescent, or luminescent
layer

- 2 430/273.1 (0 OR, 2 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
 COMPOSITION, OR PRODUCT THEREOF
 430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
 RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR
- OR
- 430/270.1 .PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
 .Radiation sensitive composition or product or
 process of making
 430/271.1 ..Identified backing or protective layer
 containing
 430/273.1 ...Identified overlayer on radiation-sensitive
 layer
- 2 430/281.1 (0 OR, 2 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
 COMPOSITION, OR PRODUCT THEREOF
 430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
 RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
 PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
 430/270.1 .Radiation sensitive composition or product or
 process of making
 430/281.1 ..Radiation sensitive composition comprising
 ethylenically unsaturated compound
- 2 430/288.1 (0 OR, 2 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
 COMPOSITION, OR PRODUCT THEREOF
 430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
 RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR
- OR
- 430/270.1 .PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
 .Radiation sensitive composition or product or
 process of making
 430/281.1 ..Radiation sensitive composition comprising
 ethylenically unsaturated compound
 430/288.1 ...Plural, terminal unsaturation
- 2 430/319 (0 OR, 2 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
 COMPOSITION, OR PRODUCT THEREOF
 430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
 RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
 PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
 430/311 .Making electrical device
 430/319 ..Named electrical device
- 2 430/325 (0 OR, 2 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
 COMPOSITION, OR PRODUCT THEREOF
 430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
 RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
 PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
 430/322 .Forming nonplanar surface
 430/325 ..Post image treatment to produce elevated
 pattern
- 2 430/327 (0 OR, 2 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
 COMPOSITION, OR PRODUCT THEREOF
 430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
 RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR
 PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT

430/327 .Processing feature prior to imaging

2 430/945 (0 OR, 2 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
 COMPOSITION, OR PRODUCT THEREOF
 430/945 LASER BEAM

2 473/378 (0 OR, 2 XR)
 Class 473 : GAMES USING TANGIBLE PROJECTILE
 473/131 GOLF
 473/351 .Ball
 473/378 ..Particular cover (e.g., size, material,
 dimple pattern, etc.)

2 522/100 (0 OR, 2 XR)
 Class 522 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
 OF THE CLASS 520 SERIES
 522/1 .COMPOSITIONS TO BE POLYMERIZED BY WAVE ENERGY
 WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
 MATERIAL; OR COMPOSITIONS TO BE MODIFIED BY WAVE ENERGY
 WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
 MATERIAL; OR PROCESSES OF PREPARING OR TREATING A SOLID
 POLYMER UTILIZING WAVE ENERGY
 522/100 ..Processes involving an ethylenically
 unsaturated material derived from poly 1,2-epoxide as
 reactant or a solid polymer; or compositions thereof

2 522/15 (0 OR, 2 XR)
 Class 522 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
 OF THE CLASS 520 SERIES
 522/1 .COMPOSITIONS TO BE POLYMERIZED BY WAVE ENERGY
 WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
 MATERIAL; OR COMPOSITIONS TO BE MODIFIED BY WAVE
 ENERGY
 WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
 MATERIAL; OR PROCESSES OF PREPARING OR TREATING A
 SOLID
 POLYMER UTILIZING WAVE ENERGY
 522/6 ..Compositions to be polymerized or modified by
 wave energy wherein said composition contains at least
 one
 specified rate-affecting material; or processes of
 preparing or treating a solid polymer utilizing wave
 energy
 in the presence of at least one specified
 rate-affecting
 material; e.g., nitrogen containing photosensitizer,
 oxygen
 containing photoinitiator, etc. wave energy in order
 to
 prepare a cellular product
 522/7 ...Contains two or more rate-affecting
 materials, at least one of which is specified
 522/12Contains compound containing keto group not
 part of a ring and a specified rate-affecting material;
 or
 contains a specified rate-affecting material and a
 nonspecified photoinitiator or photosensitizer
 522/15Specified rate-affecting material contains
 onium group

2 522/28 (1 OR, 1 XR)
 Class 522 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART

OF THE CLASS 520 SERIES

522/1

.COMPOSITIONS TO BE POLYMERIZED BY WAVE ENERGY
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
MATERIAL; OR COMPOSITIONS TO BE MODIFIED BY WAVE

ENERGY

WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
MATERIAL; OR PROCESSES OF PREPARING OR TREATING A

SOLID

522/6

POLYMER UTILIZING WAVE ENERGY
..Compositions to be polymerized or modified by
wave energy wherein said composition contains at least

one

specified rate-affecting material; or processes of
preparing or treating a solid polymer utilizing wave

energy

rate-affecting

in the presence of at least one specified

oxygen

material; e.g., nitrogen containing photosensitizer,

containing photoinitiator, etc. wave energy in order to
prepare a cellular product

522/7

...Contains two or more rate-affecting
materials, at least one of which is specified

522/28

....Specified rate-affecting material contains
phosphorous, arsenic, antimony or nitrogen

2 522/29

(0 OR, 2 XR)

Class

522 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
OF THE CLASS 520 SERIES

522/1

.COMPOSITIONS TO BE POLYMERIZED BY WAVE ENERGY
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
MATERIAL; OR COMPOSITIONS TO BE MODIFIED BY WAVE

ENERGY

WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
MATERIAL; OR PROCESSES OF PREPARING OR TREATING A

SOLID

522/6

POLYMER UTILIZING WAVE ENERGY
..Compositions to be polymerized or modified by
wave energy wherein said composition contains at least

one

specified rate-affecting material; or processes of
preparing or treating a solid polymer utilizing wave

energy

rate-affecting

in the presence of at least one specified

oxygen

material; e.g., nitrogen containing photosensitizer,

containing photoinitiator, etc. wave energy in order to
prepare a cellular product

522/7

...Contains two or more rate-affecting
materials, at least one of which is specified

522/29

....Specified rate-affecting material is a
metal-containing organic compound

2 522/99

(0 OR, 2 XR)

Class

522 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
OF THE CLASS 520 SERIES

522/1

.COMPOSITIONS TO BE POLYMERIZED BY WAVE ENERGY
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
MATERIAL; OR COMPOSITIONS TO BE MODIFIED BY WAVE ENERGY
WHEREIN SAID COMPOSITION CONTAINS A RATE-AFFECTING
MATERIAL; OR PROCESSES OF PREPARING OR TREATING A SOLID
POLYMER UTILIZING WAVE ENERGY

522/99 ..Processes involving a polysiloxane having
ethylenic unsaturation as reactant or as solid polymer;
or
compositions therefore

- 2 526/222 (0 OR, 2 XR)
Class 526 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
OF THE CLASS 520 SERIES
526/72 .POLYMERS FROM ONLY ETHYLENIC MONOMERS OR
PROCESSES OF POLYMERIZING, POLYMERIZABLE COMPOSITIONS
CONTAINING ONLY ETHYLENIC MONOMERS AS REACTANTS OR
PROCESSES OF PREPARING
526/89 ..Polymerizing in the presence of a specified
material other than monomer
526/222 ...Material contains organic sulfur compound
- 2 528/409 (0 OR, 2 XR)
Class 528 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
OF THE CLASS 520 SERIES
528/403 .FROM HETEROCYCLIC REACTANT CONTAINING AS RING
ATOMS OXYGEN, SELENIUM OR TELLURIUM, E.G., EPOXY, ETC.
528/408 ..Polymerizing in the presence of a specified
material other than a reactant
528/409 ...Material contains a metal atom
- 2 528/90 (0 OR, 2 XR)
Class 528 : SYNTHETIC RESINS OR NATURAL RUBBERS -- PART
OF THE CLASS 520 SERIES
528/86 .FROM PHENOL, PHENOL ETHER, OR INORGANIC
PHENOLATE
528/87 ..From 1,2-epoxy-containing phenolic reactant
or with 1,2-epoxy-containing reactant
528/88 ...Polymerizing in the presence of a specified
material other than reactant
528/90Material contains a sulfur atom